ABSTRACT OF THE DISCLOSURE

        From the region near the target pattern, patterns whose
barycenter positions are not changed even if deformation
is generated due to proximity effect or coarse-and-fine
5   difference at the time of pattern forming are selected as
alignment patterns, and the barycenter positions thereof
are set as alignment reference coordinates.   Rough
alignment is carried out based on the reference position
provided in a region other than the device forming region,
10   thereby detecting the alignment pattern in the device forming
region.   Positioning is carried out such that the alignment
reference coordinates of the alignment patterns and the
center coordinates of the target pattern coincide with each
other, and the target pattern is detected.